

PATENT ABSTRACTS OF JAPAN

(11)Publication number : **51-129868**
(43)Date of publication of application : **11.11.1976**

(51)Int.Cl. **B01D 53/00**
B01J 1/14

(21)Application number :	50-053904	(71)Applicant :	FUJITSU LTD
(22)Date of filing :	07.05.1975	(72)Inventor :	ITOGA MASANAO SATO JUNJI TANIGAWA YOSHIKI FUJIWARA TOSHIYASU

(54) **A PROCESS FOR TREATMENT OF WASTE GAS**

(57)Abstract:

PURPOSE: A waste gas treatment process for simple treatment of waste gas used in processes such as those for semi-conductor industry, for example, chemical vapor phase growth process.